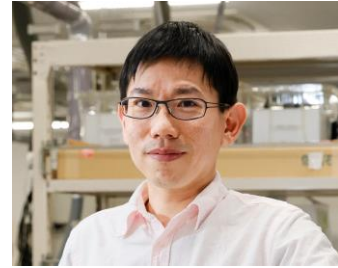




Prof. Shih-Nan Hsiao

Center for Low temperature Plasma Sciences,
Nagoya University



Shih-Nan Hsiao received his Ph.D. degree in Materials Science and Engineering from Feng Chia University, Taichung, Taiwan. In 2010, he was a visiting scholar at Argonne National Laboratory, USA, where he focused on microbeam X-ray diffraction. From 2011 to 2014, he worked as a postdoctoral fellow at the National Synchrotron Radiation Research Center, conducting research on magnetic materials using various X-ray-based techniques. Following his postdoctoral training, he spent three years in industry, working on surface treatment, coating, and finishing technologies such as arc ion plating and high-power impulse magnetron sputtering.

He is currently a Professor at the Center for Low-Temperature Plasma Sciences, Nagoya University, Japan. His research interests include cryogenic plasma etching, atomic layer etching, plasma diagnostics, and plasma simulations for semiconductor processes.

Dr. Hsiao has served as a Guest Editor for the MDPI journal *Coatings* for two years. He is currently an Editor for the Elsevier journal *Materials Chemistry and Physics* and a Guest Editor for the MDPI journal *Materials*. In addition, he is serving as a co-editor and co-author for an upcoming Elsevier book, *Plasma Processing for Semiconductor Materials and Thin Film Devices*.